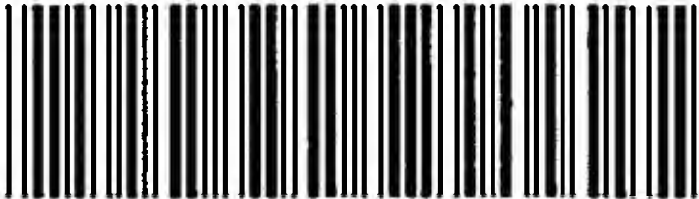


<div>Search Notes</div> <div></div>	Application/Control No.	Applicant(s)/Patent under Reexamination	
	10/707,824	LIN, LONG-HUI	
	Examiner	Art Unit	
	W. David Coleman	2823	

SEARCHED			
Class	Subclass	Date	Examiner

INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner

SEARCH NOTES (INCLUDING SEARCH STRATEGY)		
	DATE	EXMR
EAST 2.0.1 Applicants deposit a metal layer over top a dielectric then performs CMP continued	5/11/2005	WDC
-continued than scan for defects, killer and non-killer defects, text only search	5/11/2005	WDC